

Title (en)

EQUIPMENT FOR UV WAFER HEATING AND PHOTOCHEMICAL PROCESSING

Title (de)

VORRICHTUNG ZUM UV-ERHITZEN EINER HALBLEITERSCHEIBE UND ZUR PHOTOCHEMISCHEN BEHANDLUNG

Title (fr)

EQUIPEMENT DE CHAUFFE ET DE TRAITEMENT PHOTOCHEMIQUE DE TRANCHES A L'AIDE DU RAYONNEMENT ULTRAVIOLET

Publication

EP 1131845 A1 20010912 (EN)

Application

EP 98960239 A 19981116

Priority

US 9824491 W 19981116

Abstract (en)

[origin: WO0030157A1] The apparatus of the present invention provides for the dual use of a UV source to heat a substrate and to facilitate photochemistry necessary for the treatment of the substrate. The present invention also provides a method for processing a substrate by heating the substrate to a temperature above ambient via UV radiation at a first power level and conditioning the substrate by exposing the substrate to a photochemically (UV) reactive chemical, or a reactive chemical that can react with a compound on the surface of the substrate to form a photochemically reactive compound, in the presence of UV radiation at a second power level.

IPC 1-7

H01L 21/00; **H01L 21/324**

IPC 8 full level

H01L 21/00 (2006.01); **H01L 21/302** (2006.01); **H01L 21/306** (2006.01); **H01L 21/3065** (2006.01)

CPC (source: EP KR)

H01L 21/02049 (2013.01 - EP); **H01L 21/263** (2013.01 - KR); **H01L 21/67115** (2013.01 - EP)

Citation (search report)

See references of WO 0030157A1

Designated contracting state (EPC)

DE FR GB

DOCDB simple family (publication)

WO 0030157 A1 20000525; CN 1155990 C 20040630; CN 1337062 A 20020220; EP 1131845 A1 20010912; JP 2002530859 A 20020917; KR 20010107966 A 20011207

DOCDB simple family (application)

US 9824491 W 19981116; CN 98814315 A 19981116; EP 98960239 A 19981116; JP 2000583072 A 19981116; KR 20017006177 A 20010516